

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Ichiro OKABE *et al.*

Title: METHOD OF FORMING A FINE PATTERN, AND METHOD OF
MANUFACTURING A SEMICONDUCTOR DEVICE, AND A
SEMICONDUCTOR DEVICE HAVING A FINE PATTERN

Appl. No.: 09/597,161

Filing Date: 6/20/2000

Examiner: J. Diaz

Art Unit: 2815

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PROPOSED CHANGES TO THE DRAWINGS

Commissioner for Patents
Washington, D.C. 20231

Sir:

Applicants propose amending Figs. 1C, and 4C as shown in red on the attached copies. With the Examiner's approval, changes will be made to the formal drawings in due course.

Respectfully submitted,

Date 3/29/02

By [Signature]

FOLEY & LARDNER
3000 K. Street, N.W.
Suite 500
Washington, D.C.

Telephone: (202) 672-5485
Facsimile: (202) 672-5399

William T. Ellis
Attorney for Applicant
Registration No. 26,874

approved by Examiner
6/7/02

FIG. 1A

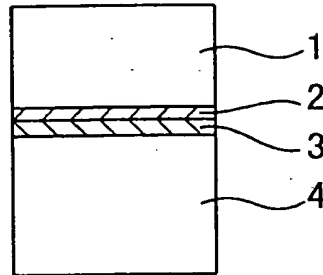


FIG. 1B

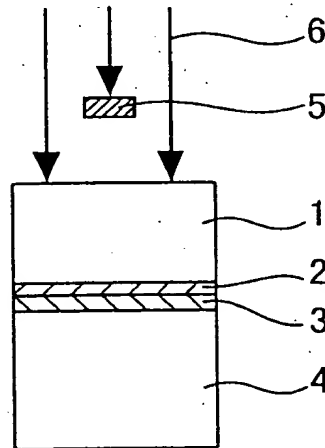


FIG. 1C

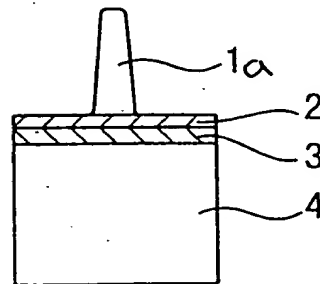


FIG. 4A

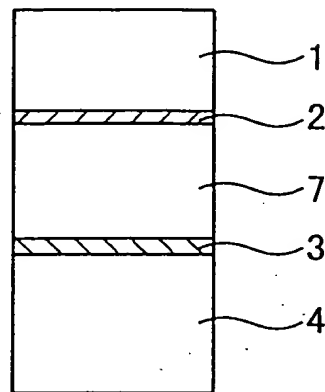


FIG. 4B

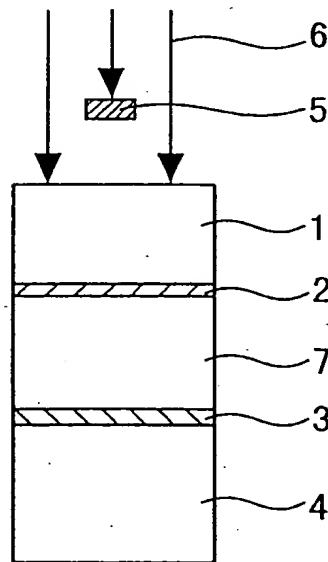


FIG. 4C

